Research Activities at UW for TTC

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- Motivation
- DC Field Emission Scanning Microscopy on Nb Samples
- High Resolution SEM/EDX for Field Emitter Identification
- Surface Roughness Measurements with OP/AFM on Nb
- Photo-induced FE for High Brightness Electron Sources
- Outlook and acknowledgments





Further progress of superconducting electron linacs towards fundamental limits requires advanced material science which can be provided by universities.

Enhanced field emission (EFE) from imperfect surfaces is a major limitation for achievable accelerating gradients in Nb cavities ($E_p = 50-120 \text{ MV/m}$!).

Local quenches and enhanced losses in high magnetic surface field regions $(H_p \rightarrow H_{crf})$ should depend on the local and average surface roughness of Nb.

Actual photocathodes used in rf guns (e.g. FLASH) provide short bunches but also high transverse emittance and have a short lifetime even under UHV. In order to avoid EFE reliably, its physical origin must be understood, e.g. by means of localisation and idenfication of emitters on samples.

The final surface quality resulting for poly/single crystalline EP & BCP Nb should be measured systematically and correlated to EFE & Quenches.

Photo-induced field emission (PFE) from flat metallic or semiconducting cathodes could lead to robust high brightness rf guns (e.g. XFEL).







DC Field Emission Scanning Microscope (FESM)



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⇒ Emitter density increases exponentially with field

⇒ <u>Activation</u> of emitters occurs at $E_{act} = (2-4) E_{on}$ probably due to burning of conducting channels into the surface oxide or removal of adsorbates.

Impact for SRF cavities:

Heating ^[1] or <u>rf power</u> might activate emitters [1] E. Mahner, Part. Acc. 46, pp.67-82 (1994)



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FESM results on single crystalline BCP/HPR-Nb from DESY

Regulated U(x,y) maps for 1 nA for scanned areas of $7.5 \times 7.5 \text{ mm}^2$ with flat W-anode $\emptyset_a = 100 \text{ }\mu\text{m}$ at anode voltage U = 4800 V electrode spacing $\Delta z = 32 \text{ }\mu\text{m}$ $\Delta z = 24 \text{ }\mu\text{m}$





mirror-like surfaces show no emission @ 120MV/m 2 emitters @ 150MV/m 5 emitters @ 200MV/m ⇒ best FE performance of all Nb samples measured yet



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SEM images of protrusion emitters (EDX \Rightarrow only Nb (+ O?))



E_{on}(2nA) < 60 MV/m ~500 μm long scratch (mishandling of sample)





 $E_{on}(2nA) = 90 \text{ MV/m}$ ~5 µm long groove $\beta = 71, S = 2.3 \cdot 10^{-6} \text{ µm}^2$

 $E_{on}(2nA) > 140 \text{ MV/m}$ ~1 μm small defect $\beta = 59, S = 7 \cdot 10^{-8} \text{ μm}^2$



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SEM/EDX of typical particulate emitters with impurities





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EFE status of actual polycrystalline HPR-Nb samples

Correlation between $E_{on}(1 \text{ nA})$ and field enhancement factor β of emitters



Typical polycrystalline Nb samples show strong EFE due to activated emitters which are either particulates or scratches of μ m height with nm sharp edges

EFE requirements on surface defects: $\beta < 50$ for FXEL and $\beta < 20$ for ILC



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Surface roughness measurements on Nb samples



Optical profilometer (OP)

white light irradiation and spectral reflection

- fast scanning speed (100×100 pixel per min)
- samples up to 20×20 cm² and 5 cm height
- 2 µm lateral and 3 nm height resolution
- atomic force microscope (AFM) operated in contact or non-contact mode
 - \bullet 2 μm positioning accuracy within OP scan
 - 34×34 µm² scanning range
 - 3 nm lateral and 1 nm height resolution
- CCD camera for positioning control
- granite plate with an active damping system for undisturbed measurement at nm scale
- clean laminar air flow from the back to reduce particulate contamination







Field emission spectrometer with UV irradiation of cathodes

UHV at 10-7 Pa

Load lock at 10⁻⁵ Pa

with ion sputtering system

In-situ exchange of Hole or mesh gate \emptyset 3 mm and rotatable cathode \emptyset 15 mm adjustable gap $\Delta z > 50 \ \mu m$ U < 20 kV \Rightarrow E < 400 MV/m

Hemispherical energy analyser $\Delta E < 50 \text{ meV}$

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TESLA TECHNOLOGY

Determination of work function Φ and T of a W needle



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electron spectra for pass energy W_{pass} and slit width w combined with integral I-V curve $\Rightarrow \Phi_{W} = -1.5 \text{ m c}^{-1} \text{ U}^{-1} = 4.39 \pm 0.3 \text{ eV}$

(literature value: $\Phi_W = 4.55 \text{ eV}$)



strong T increase of W-needle with I



Tunable OPO Laser for photo-induced FE investigations



focussing optics under construction (optional $\lambda/4$ -plate for spin polarization)





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700

1000

1500 2000

NT342B NT342A

NT342B-SH NT342A-SH

NT342B-SF/SHG

NT342A-SF/SHG

- Systematic FESM and HRSEM/EDX investigations on actual Nb samples
 A. Navitski, S. Lagotzky (BUW), A. Matheisen, D. Reschke, X. Singer (DESY)
- Correlation studies between Nb surface roughness and EFE (tomorrow)
 A. Navitski, S. Lagotzky (BUW), J. Ziegler (DESY), P. Kneisel (TJNAF)
- PFES system ready for development of flat high brightness electron sources
 B. Bornmann, S. Mingels (BUW)

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